## In the Specification:

Please amend paragraphs 2, 3, and 4 as follows:

- [2] <u>Embodiments of the The present invention relates relate</u> to a non-volatile memory cell <u>comprising including</u> dielectric layers having low dielectric constant and corresponding process.
- [3] More specifically, an <u>aspectembodiment</u> of the invention relates to a non-volatile memory cell integrated on a semiconductor substrate and <u>comprising:including</u> a floating gate transistor including a source region and a drain region, a gate region projecting from the substrate and comprised between <u>saidthe</u> source and drain regions, <u>saidthe</u> gate region having a predetermined length and width and comprising a first floating gate region and a control gate region.
- [4] Another aspectembodiment of the invention relates also to a process for manufacturing non-volatile memory cells on a semiconductor substrate, comprising the following steps:. The process includes forming active areas in saidthe semiconductor substrate bounded by an insulating layer, forming on saidthe active areas a first dielectric material layer, depositing a first conductor material layer on saidthe first dielectric layer, and definingdefine through a standard photolithographic technique a plurality of floating gate regions.

Please amend paragraph 21 as follows:

[21] A solutive idea underlying an aspectAn embodiment of the present invention is to define a process sequence needed to obtain a memory device organized in rows and columns comprising non-volatile memory cells wherein the area between two adjacent floating gate regions belonging to the same row is filled up with low dielectric constant (low-k) material.

Please delete paragraphs 22 and 23.

Please amend paragraph 24 as follows:

[24] The features and advantages of devices according to various aspects embodiments of the invention will be apparent from the following description of an embodiments thereof given by way of non-limiting example with reference to the attached drawings.